

Supporting Information

Threshold voltage tuning of IGZTO thin-film transistors deposited by RF sputtering for high-resolution flexible displays using deep ultraviolet light.

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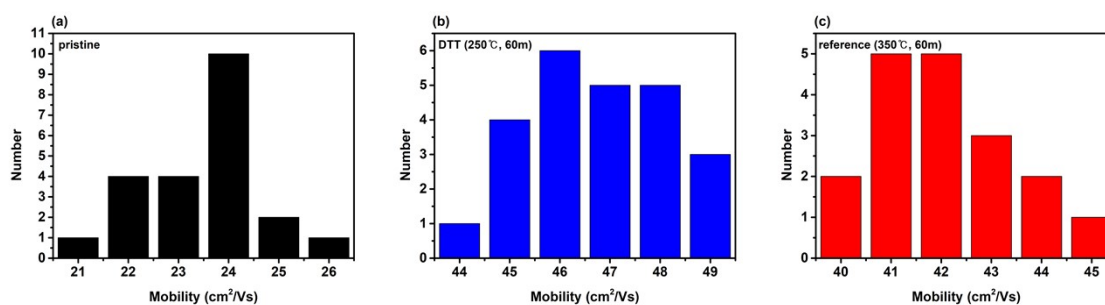


Figure S1. Mobility distributions of TFT devices with various annealing treatments applied to IGZTO thin film. (a)pristine IGZTO TFT, (b)DTT (250°C, 60m) IGZTO TFT, (c)reference (350°C, 60m) IGZTO TFT. At least 18 devices were fabricated and evaluated.

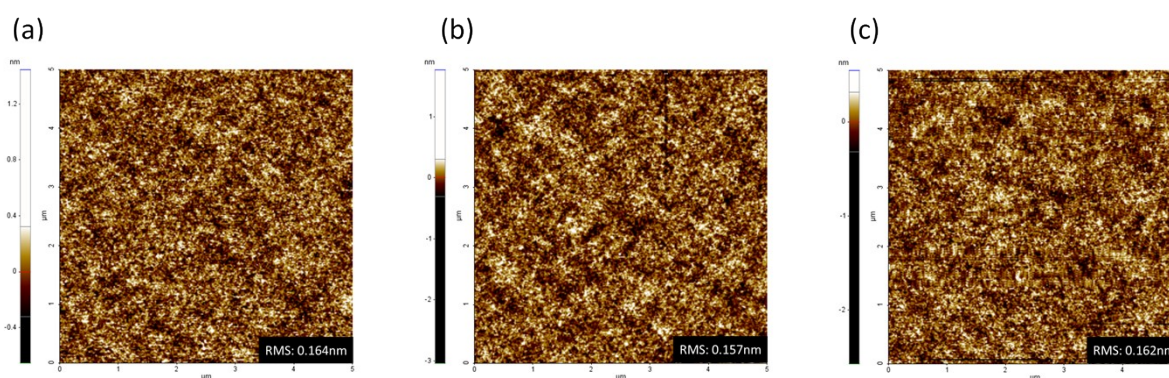


Figure S2. AFM images of (a) pristine, (b) DTT (250 °C, 60 min), and (c) reference (350 °C, 60 min), respectively.

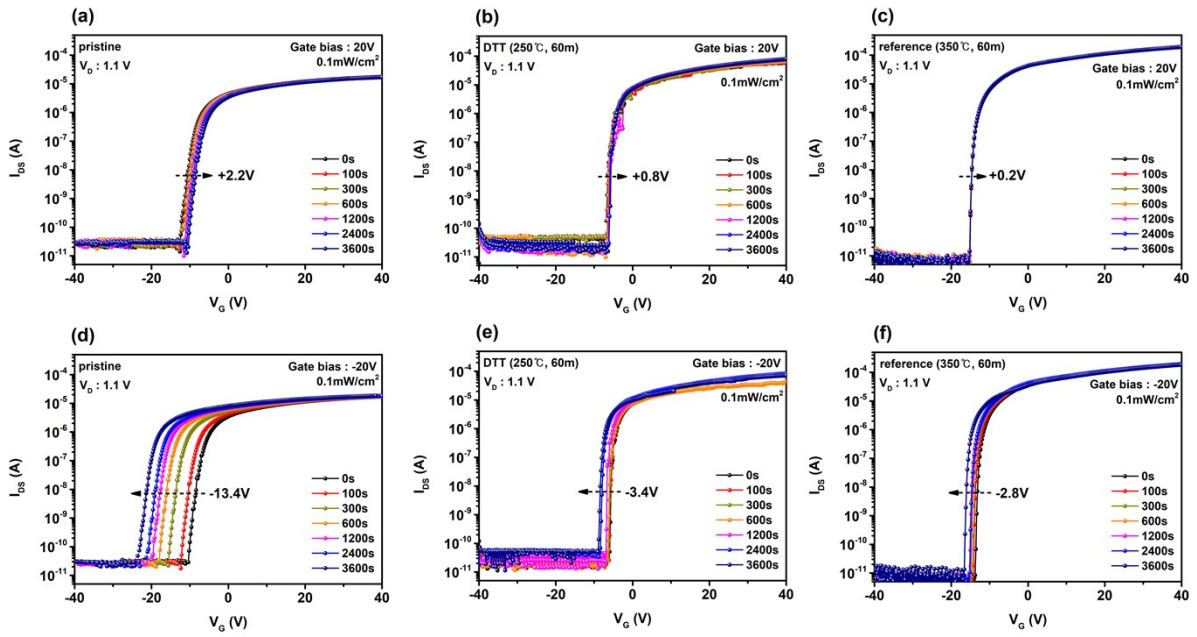


Figure S3. Positive bias illumination stress and negative bias illumination stress of (a)(d) pristine, (b)(e) DTT (250 °C, 60 min), and (c)(f) reference (350 °C, 60 min), respectively.